Supplementary Information

Realizing New Designs of Multiplexed Electrode Chips by 3-D Printed Masks

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	a)	b)	c)	d)
Xstal Start:	92.67	96.55	92.53	89.71
Xstal End:	91.61	95.18	91.88	88.48
Pressure start (Torr)	4.6 * 10 ⁻⁷	2.0 * 10 ⁻⁷	5.0 * 10 ⁻⁷	4.0 * 10 ⁻⁷
Pressure final (Torr)	5.0 * 10 ⁻⁷ /2.0 * 10 ⁻⁶	2.5 * 10 ⁻⁷ /1.0 * 10 ⁻⁶	1.5 * 10 ⁻⁶ /2.0 * 10 ⁻⁶	4.0 * 10 ⁻⁷ /1.1 * 10 ⁻⁶
Pressure max (Torr)	1.3 * 10 ⁻⁷ /3.0 * 10 ⁻⁶	9.0 * 10 ⁻⁷ /1.1 * 10 ⁻⁶	5.0 * 10 ⁻⁷ /1.1 * 10 ⁻⁶	2.0 * 10 ⁻⁷ /1.2 * 10 ⁻⁶
Adhesive Material	Cr	Ті	Ті	Ті
Adhesive Thickness	50	50	50	50
(Å)				
Adhesive Rate (Å/s)	1.0	1.0	1.0	1.0
Adhesive Current (I)	0.04	0.04	0.04	0.04
Au Thickness (Å)	1000	781	500	1000
Au Rate (Å/s)	1.5	1.5	1.0	1.0
Au Current (I)	0.03	0.08	0.04	0.04
Au Start (g)	16.22	12.73	12.64	13.30
Au Final (g)	15.81	12.25	12.50	12.82

Table S1. Additional details for table 1. Conditions for physical vapour deposition (PVD) at Nanofabrication Kingston (NFK).

Chip Reader Fabrication

Details of Pogo Pins (P50-B1 - 16mm)

Pin Centre: 0.68mm, Min test distance: 1.27 mm, Spring Pressure: 75 g, Full Stroke: 2.65 mm, Current Rating: 3 A, Current Resistance: 50 m Ω , Plunger: Heat Treated Beryllium Copper, Barrel: Phosphor Bronze. Gold Plated, Spring: stainless steel.

3D printing Parameters

0.1 mm, 95% fill density, PLA







Fig. S2. Illustration of contact pad, connector and working electrode in the design. Contact pads are used for connecting to the instrument via chip reader (Fig. S1, red part.). Connectors were coated to control the exposed surface area of working electrodes (WEs).